

a second atomic layer doping region for diffusing said first dopant species in said first substrate, said first and second doping regions being chemically isolated from one another by an inert gas curtain; and

a loading assembly for moving said first substrate from said first doping region to said second doping region, thereby enabling deposition of a first atomic monolayer in said first doping region, followed by diffusion of said first atomic monolayer in said second doping region.

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